

What is claimed:

- 1 1. A semiconductor device comprising:
2 a pad section over an interlayer dielectric layer,
3 wherein the interlayer dielectric layer includes a first silicon oxide layer that is
4 formed by a polycondensation reaction of a silicon compound and hydrogen peroxide, and a
5 second silicon oxide layer formed over the first silicon oxide layer and containing an
6 impurity, and
7 the pad section includes a wetting layer and a metal wiring layer.
- 1 2. A semiconductor device according to claim 1, wherein the impurity contained
2 in the second silicon oxide layer is phosphorous.
- 1 3. A semiconductor device according to claim 1, wherein the metal wiring layer
2 is formed from aluminum or an aluminum alloy.
- 1 4. A semiconductor device according to claim 1, wherein the wetting layer is
2 formed from a material that is selected from titanium, cobalt, zirconium, silicon and
3 niobium.
- 1 5. A semiconductor device according to claim 1, wherein the metal wiring layer
2 includes an alloy layer that contacts the wetting layer, the alloy layer including a material
3 that forms the wetting layer and a material that forms the metal wiring layer.
- 1 6. A semiconductor device according to claim 5, wherein the alloy layer has a
2 film thickness that is two to three times greater than a film thickness of the wetting layer.
- 1 7. A semiconductor device according to claim 1, wherein the pad section does
2 not have a nitride layer.

1 8. A method for manufacturing a semiconductor device, comprising the steps
2 of:

3 (a) forming an interlayer dielectric layer, the step including:

4 (a) (1) forming a first silicon oxide layer by reacting a silicon compound and
5 hydrogen peroxide through a chemical vapor deposition method, and

6 (a) (2) forming a second porous silicon oxide layer by reacting a silicon
7 compound, at least one of oxygen and a compound including oxygen, and a
8 compound including an impurity through a chemical vapor deposition
9 method;

10 (b) forming a wetting layer over the interlayer dielectric layer;

11 (c) forming a metal wiring layer over the wetting layer; and

12 (d) forming a pad section by patterning the wetting layer and the metal wiring layer.

1 9. A method for manufacturing a semiconductor device according to claim 8,
2 further comprising, after the step (a), the step of conducting an anneal treatment at a
3 temperature of 600 – 850°C.

1 10. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the silicon compound used in the step (a) (1) is at least one type selected from an
3 inorganic silane compound including monosilane, disilane, SiH_2Cl_2 and SiF_4 , or an organo
4 silane compound including CH_3SiH_3 , tripropyl-silane and tetraethylorthosilicate.

1 11. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the step (a) (1) is conducted with the silicon compound being an inorganic silane
3 compound by a reduced pressure chemical vapor deposition method at a temperature of 0 –
4 20°C.

1 12. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the step (a) (1) is conducted with the silicon compound being an organo silane
3 compound by a reduced pressure chemical vapor deposition method at a temperature of 100
4 – 150°C.

1 13. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the step (a) (2) is conducted by a plasma chemical vapor deposition method at a
3 temperature of 300 – 450°C.

1 14. A method for manufacturing a semiconductor device according claim 13,
2 wherein the compound including oxygen used in the step (a) (2) is dinitrogen monoxide.

1 15. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the step (a) (2) is conducted by a chemical vapor deposition method at a
3 temperature of 300 – 550°C.

1 16. A method for manufacturing a semiconductor device according to claim 15,
2 wherein the compound including oxygen used in the step (a) (2) is ozone.

1 17. A method for manufacturing a semiconductor device according to claim 8,
2 wherein, before forming the second silicon oxide layer in the step (a) (2), the first silicon
3 oxide layer is exposed to an ozone atmosphere.

1 18. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the impurity used in the step (a) (2) is phosphorous.

1 19. A method for manufacturing a semiconductor device according to claim 8,
2 wherein the metal wiring layer is provided by forming a first aluminum layer including
3 aluminum or an alloy containing aluminum as a main component at a temperature of 200°C
4 or lower, then forming a second aluminum layer including aluminum or an alloy containing
5 aluminum as a main component at a temperature of 300°C or higher.

1 20. A method for manufacturing a semiconductor device, comprising:
2 forming a first silicon oxide layer using a polycondensation reaction of a silicon
3 compound and hydrogen peroxide;
4 forming a second silicon oxide layer including an impurity therein; and
5 forming a pad section over the first silicon oxide layer and the second silicon oxide
6 layer, the pad section including a wetting layer and a wiring layer.

1 21. A method as in claim 20, comprising forming the second silicon oxide layer
2 to be more porous than the first silicon oxide layer.